	L #	Hits	Search Text
1	L1	111055	(mask or reticle) and (substrate or wafer)
2	L2	41262	(sampl$3 with (shot or area))
3	L3	41262	(sampl$3 with (shot or area))
4	L4	1215	3 same align$4
5	L5	263	4 and 1
6	L6	420224	(distanc$3 or interval or length) with (short$3 or quick$3 or minim$4)
7	L7	89	5 and 6
8	L8	48	7 and (355/$.ccls. or 356/$.ccls. or 430/$.ccls.)
9	L9	425418	(sequenc$3 or order$3) with (expos$4 or process$3)
10	L10	353409	(position$3 or locat$4) with (shot or area)
11	L11	7435	9 and 10 and 1
12	L12	15564	9 and 10 and 6

	L #	Hits	Search Text
13	L13	2171	1 and 12
14	L14	504	13 and (355/$.ccls. or 356/$.ccls. or 430/$.ccls.)
15	L15	404	14 and align$4
16	L16	158326	(sequenc$3 or order$3) with (sampl$3 or align$4)
17	L17	159872	15 adn 16
18	L18	194	15 and 16

PKm 3/11/03